

	Type	Ref #	Hits	Search Text
1	IS&R	S1	1411	(430/314).CCLS.
2	BRS	S2	439461	etch\$3
3	BRS	S3	621201	photoresist or resist or photosensitive
4	BRS	S4	335480	plasma
5	BRS	S5	12610	S4 near5 S3
6	BRS	S6	9897	S5 same S2
7	BRS	S7	3784	S6 and carbon
8	BRS	S8	4507	carbon adj radicals
9	BRS	S9	621585	photoresist or resist or photosensitive
10	BRS	S10	298	S9 and S8
11	BRS	S11	933	RF adj bias adj power
12	IS&R	S12	1	("6326307").PN.
13	IS&R	S13	1	("6103457").PN.
14	IS&R	S14	1	("5562801").PN.
15	BRS	S17	666147	silicon
16	BRS	S18	1146306	carbon
17	BRS	S19	440466	etch\$3
18	BRS	S20	76909	S19 near5 S17
19	BRS	S21	336525	plasma
20	BRS	S22	622261	photoresist or resist or photosensitive
21	BRS	S23	2984	S22 same S21 same S18

	Type	Ref #	Hits	Search Text
22	BRS	S24	1440	S20 and S23
23	BRS	S25	1401083	treat\$3 or pretreat\$3
24	BRS	S26	363	S25 and S24
25	BRS	S27	64	S26 and carbon adj dioxide